Form PTO-1449 (Modified)	Atty Docket No.	Serial No.
LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT	H1559	10/790,457
(Use several sheets if necessary)	Applicant: Pawloski	
	Filing Date 03/01/04	Group 1756

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U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Class	Sub-class	Filing Date if Appropriate
COS	5,610,683	03/11/97	Takahashi	355	53	
COS	5,900,354	05/04/99	Batchelder	430	395	
COS	6,024,801	02/15/00	Wallace et al.	134	1	
COS	6,602,349 B1	08/05/03	Chandra et al.	134	19	
COS	6,612,317 B2	09/02/03	Costantini et al.	134	58	
COS	2002/0163629 A1	11/07/02	Switkes et al.	355	53	
COS	2003/0064604 A1	04/03/03	Umeda	438	745	
COS	2003/0123040 A1	07/03/03	Almogy	355	69	
COS	2003/0174408 A1	09/18/03	Rostalski et al.	359	642	

FOREIGN PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Country	Class	Sub-class	Translation Yes	Translation No
COS	0 822 583 A2	04/02/98	EP	—	—		
COS	0 829 312 B1	04/06/03	EP	—	—		

OTHER ART

Examiner Initial	Author, Title, Date, Pertinent Pages, etc.
COS	Switkes et al.; "Immersion Lithography at 157 nm"; J. Vac. Sci. Technol. B 19(6), Nov./Dec. 2001; pp. 2353-2356.
COS	Smith et al.; "Immersion Optical Lithography at 193 nm"; Rochester Institute of Technology; Future Fab Int'l, Vol. 15 (07/11/2003).
COS	Goldfarb et al.; "Aqueous-based Photoresist Drying Using Supercritical Carbon Dioxide to Prevent Pattern Collapse"; J. Vac. Sci. Technol. B 18(6), Nov./Dec. 2000; pp. 3313-3317.
COS	Jincao et al.; "Prevention of Photoresist Pattern Collapse by Using Liquid Carbon Dioxide"; Ind. Eng. Chem. Res. 2001, 40, pp. 5858-5860.
COS	Sundararajan et al.; "Supercritical CO_2 Processing for Submicron Imaging of Fluoropolymers"; Chem. Mater, 2000, 12, pp. 41-48.

EXAMINER	DATE CONSIDERED
	10/25/06

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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Information Disclosure Statement PTO-1449 (Modified)

The identification of any reference is not intended to be, and should not be understood as being, an admission that such publication, in fact, constitutes "prior art" within the meaning of applicable law since, for example, a given reference may have a later effective date than first seems apparent or the reference may have an effective date which can be antedated. The "prior art" status of any reference is a matter to be resolved during prosecution.

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